

ABSTRACT

An objective of the present invention is to provide a phosphorous-containing siliceous material having a specific  
5 permittivity of not more than 3.5. The phosphorus-containing  
silazane composition according to the present invention is  
characterized by comprising a polyalkylsilazane and at least one  
phosphorus compound in an organic solvent. A  
phosphorus-containing siliceous film may be formed by coating  
10 the composition onto a substrate to form a film which is then  
prebaked at a temperature of 50 to 300°C and is then baked in  
an inert atmosphere at a temperature of 300 to 700°C. The  
phosphorus compound according to the present invention is  
preferably a pentavalent phosphoric ester or phosphazene  
15 compound.